

# Quantum Anomalous Hall Effect Devices for Resistance Metrology

Dinesh K. Patel\*, Mattias Kruskopf\*, Martin Götz\*, Eckart Pesel\*, Hansjörg Scherer\*, Kajetan M. Fijalkowski<sup>§‡</sup>, Steffen Schreyeck<sup>§‡</sup>, Karl Brunner<sup>§‡</sup>, Charles Gould<sup>§‡</sup>, Laurens W. Molenkamp<sup>§‡</sup>

\*Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany

§Physikalisches Institut (EP3), Universität Würzburg, Am Hubland, 97074 Würzburg, Germany

‡Institute for Topological Insulators, Am Hubland, 97074 Würzburg, Germany

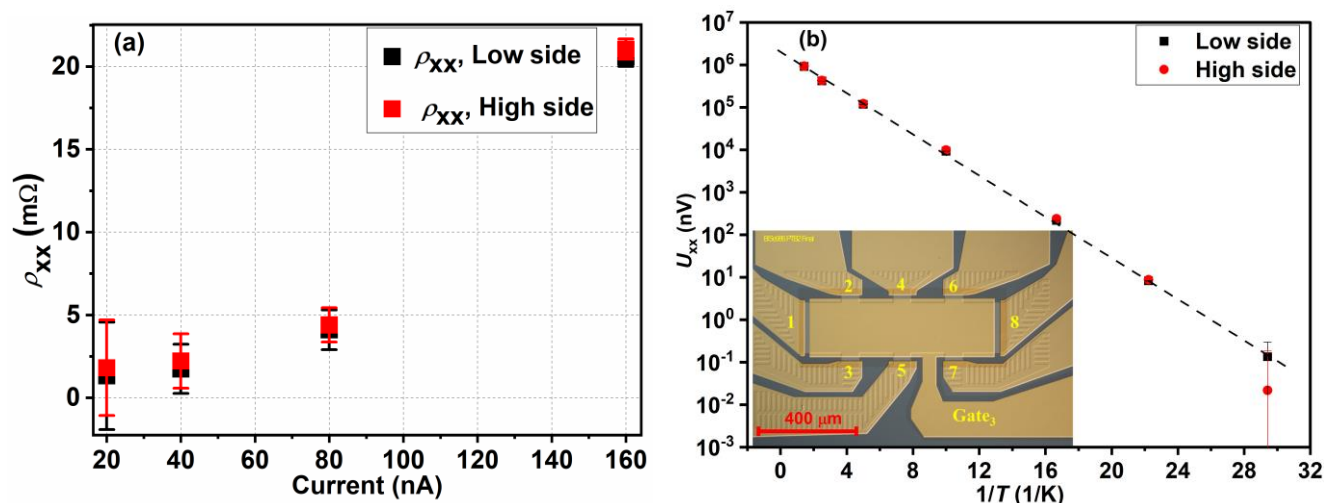
dinesh.patel@ptb.de

Abstract: The quantum anomalous Hall effect (QAHE), as manifested in ferromagnetically-doped topological insulator (TI) materials [1, 2] is of high interest in fundamental physics and in metrology. For metrology, the effect has enormous potential because it provides Hall resistance quantization in units of the von-Klitzing constant in zero external magnetic field. We have extensively characterized Hall-bar-shaped devices from V-doped  $(\text{BiSb})_2\text{Te}_3$  by means of a state-of-the-art precision resistance bridge based on a 14-bit cryogenic current comparator (CCC) at PTB [3]. In comparison with former experiments using a 12-bit CCC bridge, the 14-bit CCC bridge has a significantly improved resolution, especially at low currents in the nA range. Our latest experiments include current and temperature dependent measurements of magneto-transport quantities in the QAHE regime, performed on recently fabricated devices with improved contact technology. The results to be presented at the conference clearly show improved results at higher currents compared to previous investigations on V-doped  $(\text{BiSb})_2\text{Te}_3$  devices [1].

## References

- [1] Martin Götz, Kajetan M. Fijalkowski, Eckart Pesel, Matthias Hartl, Steffen Schreyeck, Martin Winnerlein, Stefan Grauer, Hansjörg Scherer, Karl Brunner, Charles Gould, Franz J. Ahlers<sup>1</sup>, Laurens W. Molenkamp, *Appl. Phys. Lett.* 112, (2018) 072102
- [2] Yuma Okazaki, Takehiko Oe, Minoru Kawamura, Ryutaro Yoshimi, Shuji Nakamura, Shintaro Takada, Masataka Mogi, Kei S. Takahashi, Atsushi Tsukazaki, Masashi Kawasaki, Yoshinori Tokura, Nobu-Hisa Kaneko, *Nat. Phys.* 18, (2022) 25
- [3] D. Drung, M. Götz, E. Pesel, H. Scherer, *IEEE Transactions on Instrumentation and Measurement* 64, (2015) 3021

## Figures



**Figure 1:** (a) It shows the current dependence of the longitudinal resistivity. (b) Arrhenius plot of the temperature dependent longitudinal voltage obtained at a current of  $\pm 40$  nA, a gate voltage of 5.8 V and a measurement time of 32 minutes. The inset is the optical image of an as-fabricated device with labeled contacts.